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APPLICATION NO.	FILING DATE	FIRST NAMED INVENTOR	ATTORNEY DOCKET NO.	CONFIRMATION NO.
10/718,487	11/20/2003	George G. Barclay	51854	8441
7590 06/02/2006			EXAMINER	
EDWARDS & ANGELL, LLP P.O. Box 9169			SCHILLING, RICHARD L	
Boston, MA 0	2209		ART UNIT	PAPER NUMBER
,			1752	
			DATE MAILED: 06/02/2006	

Please find below and/or attached an Office communication concerning this application or proceeding.

	Application No.	Applicant(s)				
	10/718,487	BARCLAY ET AL.				
Office Action Summary	Examiner	Art Unit				
·	Richard L. Schilling	1752				
The MAILING DATE of this communication appears on the cover sheet with the correspondence address						
Period for Reply						
A SHORTENED STATUTORY PERIOD FOR REPL WHICHEVER IS LONGER, FROM THE MAILING D - Extensions of time may be available under the provisions of 37 CFR 1.1 after SIX (6) MONTHS from the mailing date of this communication. - If NO period for reply is specified above, the maximum statutory period - Failure to reply within the set or extended period for reply will, by statute Any reply received by the Office later than three months after the mailin earned patent term adjustment. See 37 CFR 1.704(b).	ATE OF THIS COMMUNICA 36(a). In no event, however, may a rep will apply and will expire SIX (6) MONTH e, cause the application to become ABAI	ATION. ly be timely filed HS from the mailing date of this communication. NDONED (35 U.S.C. § 133).				
Status						
1) Responsive to communication(s) filed on 06 h	<u>farch 2006</u> .					
2a) ☐ This action is FINAL . 2b) ☑ This	This action is FINAL . 2b)⊠ This action is non-final.					
) Since this application is in condition for allowance except for formal matters, prosecution as to the merits is						
closed in accordance with the practice under Ex parte Quayle, 1935 C.D. 11, 453 O.G. 213.						
Disposition of Claims						
4)⊠ Claim(s) <u>1,2,5,22-24,52 and 62-70</u> is/are pending in the application.						
4a) Of the above claim(s) is/are withdrawn from consideration.						
5) Claim(s) is/are allowed.						
, <u> </u>	6) Claim(s) <u>1,2,5,22-24,52,62-70</u> is/are rejected.					
,	7) Claim(s) is/are objected to.					
8) Claim(s) are subject to restriction and/or election requirement.						
Application Papers						
9)☐ The specification is objected to by the Examine	er.					
10) ☐ The drawing(s) filed on is/are: a) ☐ accepted or b) ☐ objected to by the Examiner.						
Applicant may not request that any objection to the drawing(s) be held in abeyance. See 37 CFR 1.85(a). Replacement drawing sheet(s) including the correction is required if the drawing(s) is objected to. See 37 CFR 1.121(d).						
Replacement drawing sheet(s) including the correct 11) The oath or declaration is objected to by the E						
The path of declaration is objected to by the E.	xammer. Note the attached	Office Action of form 1 10-102.				
Priority under 35 U.S.C. § 119						
12) Acknowledgment is made of a claim for foreign priority under 35 U.S.C. § 119(a)-(d) or (f).						
a) All b) Some * c) None of:						
1. Certified copies of the priority documents have been received.						
 2. Certified copies of the priority documents have been received in Application No 3. Copies of the certified copies of the priority documents have been received in this National Stage 						
3. Copies of the certified copies of the priority documents have been received in this National Stage application from the International Bureau (PCT Rule 17.2(a)).						
* See the attached detailed Office action for a list of the certified copies not received.						
Attachment(s)						
1) Notice of References Cited (PTO-892) 2) Notice of Draftsperson's Patent Drawing Review (PTO-948) 4) Interview Summary (PTO-413) Paper No(s)/Mail Date						
3) Information Disclosure Statement(s) (PTO-1449 or PTO/SB/08 Paper No(s)/Mail Date		ormal Patent Application (PTO-152)				

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1. A request for continued examination under 37 CFR 1.114, including the fee set forth in 37 CFR 1.17(e), was filed in this application after final rejection. Since this application is eligible for continued examination under 37 CFR 1.114, and the fee set forth in 37 CFR 1.17(e) has been timely paid, the finality of the previous Office action has been withdrawn pursuant to 37 CFR 1.114. Applicant's submission filed on 3-06-06 has been entered.

The following is a quotation of 35 U.S.C. 103(a) which forms the basis for all obviousness rejections set forth in this Office action:

- (a) A patent may not be obtained though the invention is not identically disclosed or described as set forth in section 102 of this title, if the differences between the subject matter sought to be patented and the prior art are such that the subject matter as a whole would have been obvious at the time the invention was made to a person having ordinary skill in the art to which said subject matter pertains. Patentability shall not be negatived by the manner in which the invention was made.
- 2. Claims 1, 2, 5, 22-24, 52 and 62-71 are rejected under 35 U.S.C. 103(a) as being unpatentable over the combination of Brock et al. and Sinta et al. Brock et al. (col. 4, lines 38-51; col. 1, lines 31-41; col. 2, lines 46-63) discloses bilayer photoresists with antireflection and etchable organic polymer underlayers and photoresist layers of Si polymers and photoacids. The underlayers are suitable for absorbing deep uv radiation. Sinta et al. (col. 3, line 35-col.4, line67; col. 7, lines 5-35; col. 9, lines 3-15) discloses bilayer photoresists with underlayers for absorbing deep uv radiation comprising polymers with aromatic absorbing groups with other polymers with phenol groups as etchable antireflection layers and photoresist layers sensitive to deep uv radiation. It would be obvious to one skilled in the art to use the Si containing polymer containing photoresist layers of Brock et al. as the called for deep uv sensitive

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photoresist top layers in Sinta et al. or to use the underlayers of Sinta et al. as the called for underlayers in Brock et al. as antireflection layers for deep uv radiation.

3. Claim 53 should be indicated as canceled in the next amendment or response.

.Any inquiry concerning this communication should be directed to Richard L. Schilling at telephone number 571-272-1335.

RICHARD L. SCHILLING PRIMARY EXAMINER

GROUP #160 / 7